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Duan et al.

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(54) **LASER MICRO/NANO PROCESSING SYSTEM AND METHOD**

(71) Applicant: **Technical Institute of Physics and Chemistry of the Chinese Academy of Sciences, Beijing (CN)**

(72) Inventors: **Xuanming Duan, Beijing (CN); Shu Chen, Beijing (CN); Hongzhong Cao, Beijing (CN); Xianzi Dong, Beijing (CN); Zhensheng Zhao, Beijing (CN)**

(73) Assignee: **Technical Institute of Physics and Chemistry of the Chinese Academy of Sciences, Beijing (CN)**

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Primary Examiner — Brook Kebede

(74) *Attorney, Agent, or Firm* — Rankin, Hill & Clark LLP

(57) **ABSTRACT**

A laser micro/nano processing system (100, 200, 300, 400) comprises: a laser light source used to provide a first laser beam having a first wavelength and a second laser beam having a second wavelength different from the first wavelength, with the pulse width of the first laser beam being in the range from a nanosecond to a femtosecond; an optical focusing assembly used to focus the first laser beam and the second laser beam to the same focal point; and a micro mobile platform (21) controlled by a computer. Also disclosed are a method for micro/nano-processing photosensi-

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